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	Application No.	Applicant(s)	
Notice of Allowability	09/759,909	LIM	
	Examiner	Art Unit	
	PHUC T. DANG	2818	
The MAILING DATE of this communication appearance All claims being allowable, PROSECUTION ON THE MERITS IS herewith (or previously mailed), a Notice of Allowance (PTOL-85) NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT Report of the Office or upon petition by the applicant. See 37 CFR 1.313	(OR REMAINS) CLOSED in or other appropriate committee committee in the committee of the com	n this application. If not including the including the industrial in displaying the industrial indu	uded ue course. THIS
1. This communication is responsive to <u>January 16, 2001</u> .			
2. The allowed claim(s) is/are <u>1-31</u> .			
3.	e been received. e been received in Application cuments have been received of this communication to file MENT of this application.  Initted. Note the attached EX es reason(s) why the oath of the submitted. Initted son's Patent Drawing Review of the submitted of	on No  d in this national stage application of the drawings in the front (not FR 1.121(d).	requirements r NOTICE OF
<ul> <li>Attachment(s)</li> <li>1. ☑ Notice of References Cited (PTO-892)</li> <li>2. ☐ Notice of Draftperson's Patent Drawing Review (PTO-948)</li> <li>3. ☑ Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date 040601</li> <li>4. ☐ Examiner's Comment Regarding Requirement for Deposit of Biological Material</li> </ul>	6. ☐ Interview S Paper No. 7. ☐ Examiner's 8. ☑ Examiner's 9. ☐ Other		Allowance
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## **DETAILED ACTION**

## Examiner's Statement of Reasons for Allowance

- 1. Claims 1-31 are allowed.
- 2. The following is an examiner's statement of reasons for allowance:

None of the prior art teaches a method to form shallow trench isolation in the manufacture of an integrated circuit device, comprising the step of polishing down the trench oxide layer and the polysilicon layer stopping at the silicon nitride layer to complete the shallow trench isolations in the manufacture of the integrated circuit in combination with the other steps found in each of the independent method claims 1, 14 and 24.

- 3. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submission should be clearly labeled "Comments on Statement of Reasons for Allowance".
- 4. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Phuc T. Dang whose telephone number is (571) 272-1776. The examiner can normally be reached on 8:00 am-5:00 pm.
- 5. If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David C. Nelms can be reached on (571) 272-1787. The fax phone numbers for the organization where this application or proceeding is assigned are 571-273-8300 for regular communications and After Final communications.

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6. Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist whose telephone number is 703-308-0956.

Phuc T. Dang

Primary Examiner

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